INFORMATION DISCLOSURE CITATION PTO-1449 Atty. Docket No. 010819

Serial No. 09/891,511

Applicant: Mamoru NAKASUJI et al.

Filing Date: June 27, 2001

Group Art Unit: 2812

## U.S. PATENT DOCUMENTS

Examiner Initial P 6		Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)
100	A P	6,125,522	Nakasuji	10/03/00			11/12/96
ANN 182	W <sub>XX</sub>	6,087,667	Nakasuji et al.	07/11/00			09/30/97
<b>7</b>	ARR	5,994,704	Nakasuji	11/30/99			10/03/97
HAGEN	AZ	5,981,947	Nakasuji etal.	11/09/99			02/03/98
20	BA	5,892,224	Nakasuji	04/06/99			05/09/97
910	BC	5,770,863	Nakasuji	06/23/98			10/24/96
910	BD	5,763,893	Nakasuji	06/09/98			12/16/96
AR	BE	5,751,538	Nakasuji	05/12/98			09/26/96
912	BF	5,747,819	Nakasuji et al.	05/05/98			10/30/96
9/3	BG	5,362,968	Miyoshi et al.	11/08/94			09/27/93
912	ВН	5,359,197	Komatsu et al.	10/25/94			07/16/93
JB.	BI	4,912,052	Miyoshi et al.	03/27/90			09/23/88

## OTHER DOCUMENTS

BI Low Voltage and high speed operation that the speed operation of the speed operation operation of the speed operation oper

Low Voltage and high speed operating electrostatic wafer chuck using sputtered tantalum oxide membrane, Mamoru Nakasuji et al., J. Vac. Sci. Technol. A 12(5), Sep/Oct 1994, American Vacuum Society pp. 2834-2839.

High-Emittance and Low-Brightness Electron Gun for Reducing-Image Projection System: Computer Simulation, Mamoru Nakasuji et al., Jpn. J. Appl. Phys. Vol. 36 (1997) pp.2404-2408.

H. Hayashi, et al., LSI Testing Symposium 1998, Minutes of the meeting, P160 (1998) (partial translation)

INFORMATION DISCLOSURE CITATION PTO-1449

Serial No. 09/891,511 Atty. Docket No. 010819

Applicant: Mamoru NAKASUJI et al.

Filing Date: June 27, 2001 Group Art Unit: 2812

## FOREIGN PATENT DOCUMENTS

JAH T B 20102		Document No.	Date	Country	Translation (Yes or No)
-90	AA	52-115161	09/27/77	JAPAN	ABSTRACT
The state of the s	AB	52-117567	10/03/77	JAPAN	ABSTRACT
98	AC	57-072326	05/06/82	JAPAN	ABSTRACT
910	AD	57-125871	08/05/82	JAPAN	ABSTRACT
910	AE	60-000741	01/05/85	JAPAN	ABSTRACT
910	AF	62-195838	08/28/87	JAPAN	ABSTRACT
110	AG	03-022339	01/30/91	JAPAN	ABSTRACT
913	AH	03-053439	03/07/91	JAPAN	ABSTRACT
910	AI	03-102814	04/30/91	JAPAN	ABSTRACT
910	AJ	03-266350	11/27/91	JAPAN	ABSTRACT
GD_	AK	03-276548	12/06/91	JAPAN	ABSTRACT
600	AL	04-266350	09/22/92	JAPAN	ABSTRACT
43	AM	05-063261	03/12/93	JAPAN	ABSTRACT
910	AN	05-251316	09/28/93	JAPAN	ABSTRACT
910	AO	07-065766	03/10/95	JAPAN	ABSTRACT
All .	AP	08-138611	05/31/96	JAPAN	ABSTRACT
GIO_	AQ	09-311112	12/02/97	JAPAN	ABSTRACT
910	AR	10-062503	03/06/98	JAPAN	ABSTRACT
999	AS	10-177952	06/30/98	JAPAN	ABSTRACT
All n	AT	11-132975	05/21/99	JAPAN	ABSTRACT
910	AU	2000-090868	03/31/00	JAPAN	ABSTRACT
1910 1	AV	07-249393	09/26/95	JAPAN	ABSTRACT

Examiner

Jack Berman

Date Considered 9/25/03

	Examiner			Date Considered					
	INFOR DISCI			Atty. Docket No. 010819 Serial No. 09/891,511					
		ATION		Applicant: Mamoru NAKASUJI et al.					
		)-1449		Filing Date: June 27, 2001 Group Art Unit:					
OTHER DOCUMENTS									
CITE .	JAN 1 8 7007	BM BN BO	Applie  An ele  Vac. S  3009.  Requir  inspec	Beam Concepts for Nanometer Devices, B. Lischke et al., Japanese Journal of ed Physics, Vol. 28, No.10, October 1989, pp. 2058-2064.  ctron-beam inspecting system for x-ray mask production, P. Sandland et al., J. Sci. Technol. B9 (6), Nov/Dec. 1991, American Vacuum Society, pp.3005-rements and performance of an electron-beam column designed for x-ray mask tion, W.D. Meisburger et al., J. Vac. Sci. Technol. B9 (6), Nov/Dec 1991, ean Vacuum Society, pp.3010-3014.					
	BP Table 5- BQ BR BS			5-1 Work Function in Metals page 116.					
	Examiner	gack	Be	nman Date Considered 9/	125103				

CITATION PTO 1459		Applic	ant(s): NA	KASUJI, e	t al.				
		Filing Date: June 27, 2001			Group Art Unit: 2812				
	FEB 1 17	35		U.S. PA	TENT DO	CUMEN	TS		
Examiner Initial	ENT 3 TR	Docum	ent No.	Name		Date	Class	Subclass	Filing Date (If appropriate)
20	AA	4,944,6	45	Suzuki		7/31/90			
	AB								
	AC								
			F	OREIGN	PATENT I	OCUM	ENTS		
		Docum	ent No.		Date		Country		Translation (Yes or No)
913	AD	JP 200	0-67798	Α	03/03	3/2000	Japan		Abstract only
910	AE	JP 9-73	3872 A		03/18	3/1997	Japan		Abstract only
400	AF	JP 63-0	6737 A		01/12	2/1988	Japan		Abstract only
200	AG	JP 200	0-10036	9 A	04/07	7/2000	Japan		Abstract only

Serial No. 09/891,511

Atty. Docket No. 010819

JP 2000-3692 A

JP 62-100936 A

JP 10-125271 A

JP 11-233062 A

AK

JP 2000-133565 A

INFORMATION

DISCLOSURE

		OTHER DOCUMENTS	TECH
	AM		RECEI FEB 12
	AN		EIVED 2 200 CEDTER 2800
Examiner	ach	Bounda / Date Considered 9/25/03	

01/07/2000

05/12/2000

05/11/1987

05/15/1998

08/27/1999

Japan

Japan

Japan

Japan

Japan

Abstract only

Abstract only

Abstract only

Abstract only

Abstract only